

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	610	(polishing near5 composition near5 method).ti.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 13:25
S2	1536	uotani.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 13:26
S3	342622	takahashi.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 13:26
S4	417420	sato.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 13:26
S5	751361	S2 S3 S4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 13:26
S6	24	S5 and S1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 13:26
S7	6	S5 and (azole same oxidizing same amino)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 13:28
S8	1	WO-03068883-\$.did.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 14:44
S9	0	S8 and oxidizing and amino and azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 14:45
S10	0	S8 and oxidizing and amino and azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 14:45
S11	2	("6776810").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/12/15 14:46
S12	1	S11 and oxidizing and amino and azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 14:46

S13	2	EP-1118647-\$.did.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:14
S14	0	S13 and oxidizing and amino and azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:15
S15	0	S13 and (oxidizing or oxidizer) and amino and azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:15
S16	3373	(oxidizing or oxidizer) and amino and azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:15
S17	169	(polishing or planarizing or planarization or abrading or abrasion).ti. and (oxidizing or oxidizer) and amino and azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:16
S18	1	WO-02067309-\$.did.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:16
S19	0	S18 and oxidizing and amino and azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:16
S20	0	S18 and (oxidizing or oxidizer) and amino and azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:16
S21	14	(polishing or planarizing or planarization or abrading or abrasion).ti. and (oxidizing or oxidizer) and amino and azole same molecular near4 weight	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:50
S22	15	(polishing or planarizing or planarization or abrading or abrasion).ti. and azole same molecular near4 weight	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:52
S23	16	(polishing or planarizing or planarization or abrading or abrasion).ab. and azole same molecular near4 weight	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:52
S24	16	(polishing or planarizing or planarization or abrading or abrasion).ab. and (azole same molecular near4 weight)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:52

S25	3	(polishing or planarizing or planarization or abrading or abrasion).ti. and azole same molecular near4 mass	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:54
S26	236	(polishing or planarizing or planarization or abrading or abrasion) same azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:54
S27	18	(polishing or planarizing or planarization or abrading or abrasion) same azole same molecular	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:54
S28	662	(polishing or planarizing or planarization or abrading or abrasion).ab. and amino same (glycine or alanine or aminobutyric or proline or phenylalanine or sarcosine or ornithine or leucine or valine or norvaline or thyroxine or lanthionine or ethionine or methionine or cycteine or tyrosine or homoserine or threonine or serine or glutamine or azaserine or arginine or canavanine or citrulline or lysine or histidine or ergothioneine or tryptophan)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:57
S29	592	(polishing or planarizing or planarization or abrading or abrasion).ab. and amino near3 acid same (glycine or alanine or aminobutyric or proline or phenylalanine or sarcosine or ornithine or leucine or valine or norvaline or thyroxine or lanthionine or ethionine or methionine or cycteine or tyrosine or homoserine or threonine or serine or glutamine or azaserine or arginine or canavanine or citrulline or lysine or histidine or ergothioneine or tryptophan)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:58

S30	165	(polishing or planarizing or planarization or abrading or abrasion).ab. and amino near3 acid same (glycine or alanine or aminobutyric or proline or phenylalanine or sarcosine or ornithine or leucine or valine or norvaline or throxine or lanthionine or ethionine or methionine or cyteine or tyrosine or homoserine or threonine or serine or glutamine or azaserine or arginine or canavanine or citrulline or lysine or histidine or ergothioneine or tryptophan) same (chelating or complex or complexing or enhance)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 15:59
S31	2	("20020173221").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/12/15 16:14
S32	1	S31 and azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 16:14
S33	1	S31 and surfactant	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 16:20
S34	4	((("6776810") or ("20020173221")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/12/15 16:38
S35	1	S34 and ((film near3 forming) or "film-forming")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 16:38
S36	13915	(polishing or planarizing or planarization or abrading or abrasion).ab. and (alakli or alkaline or polyamine or ammonia)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 16:57
S37	3278	(polishing or planarizing or planarization or abrading or abrasion).ab. and (alakli or alkaline or polyamine or ammonia) same ("% " or amount)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 16:57
S38	880	(polishing or planarizing or planarization or abrading or abrasion).ab. and (alakli or alkaline) same ("% " or amount)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 16:57

S39	46	(polishing or planarizing or planarization or abrading or abrasion).ab. and (alkali or alkaline) near3 (component or substance) same ("% " or amount)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 16:57
S40	12	(polishing or planarizing or planarization or abrading or abrasion).ab. and (alkali or alkaline) near3 (component or substance) with (enhanc\$4 or improv\$4 or impart\$4 or effective or effect or increas\$4 or decreas\$4 or benefit or better or exhibit or prefer or preferred or effective) same ("% " or amount)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 17:04
S41	101	(polishing or planarizing or planarization or abrading or abrasion) same (alkali or alkaline) near3 (component or substance) same ("% " or amount)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 17:11
S42	43	(polishing or planarizing) same (alkali or alkaline) near3 (component or substance) same ("% " or amount)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/15 17:11
S43	90734	(surfactant or (surface near2 active) or "surface-active") same (alkylaromatic or sulfonic or polyoxyethylene or phosphoric)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 09:15
S44	693	(surfactant or (surface near2 active) or "surface-active") same (alkylaromatic or sulfonic or polyoxyethylene or phosphoric) and polishing. ti.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 09:15
S45	1892	438/427.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 09:16
S46	6144	51/307-309.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 09:16
S47	2561	451/5.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 09:16

S48	1093	106/3.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 09:16
S49	1136	216/99.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 09:16
S50	1030	216/101-102.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 09:16
S51	13337	S45 S46 S47 S48 S49 S50	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 09:17
S52	132	S51 and S44	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 09:17
S53	15	(surfactant or (surface near2 active) or "surface-active") same ((alkylaromatic near3 sulfonic) or (polyoxyethylene near3 phosphoric) or (alkyl near3 phosphoric near2 acid)) and polishing.ti.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 10:10
S54	13919	(alkali ro alkaline or polyamine or ammonia) same polishing	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 10:18
S55	968	(alkali ro alkaline or polyamine or ammonia) same polishing and S51	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 10:18
S56	682	(alkali ro alkaline or polyamine or ammonia) and polishing.ti. and S51	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 10:20
S57	296	(alkali ro alkaline or polyamine or ammonia) near10 (substance or component or compound) and polishing.ti. and S51	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 10:20
S58	252	(alkali ro alkaline or polyamine or ammonia) near5 (substance or component or compound) and polishing.ti. and S51	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 10:38

S59	109	(alkali ro alkaline or polyamine or ammonia) near5 (substance or component or compound) and (polishing near composition).ti. and S51	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 10:39
S60	0	(azole with vinyl with "water-soluble") and (polishing near composition).ti. and S51	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 11:15
S61	0	(azole with vinyl with "water-soluble") and (polishing near composition).ti.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 11:15
S62	4	(azole with vinyl with "water-soluble") and polishing.ti.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 11:15
S63	5	(azole with "water-soluble" same vinyl) and polishing.ti.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 11:15
S64	11	(azole with "water-soluble" same vinyl)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 11:16
S65	11	(azole\$4 with "water-soluble" same vinyl)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 11:18
S66	107	((benzotriazole or triazole or azole\$4) with "water-soluble" same vinyl)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 11:19
S67	94	((benzotriazole or triazole or azole\$4) with "water-soluble" with vinyl)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 11:19
S68	716	azole with polymer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 11:24
S69	44	azole with polymer with ("water-soluble" or (water near soluble))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/16 11:25
S70	2	("5976414").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/12/16 11:39

S71	92626	fatty near acid same (surfactant or (surface near active))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 12:58
S72	0	fatty near acid same (surfactant or (surface near active)) and (polishing or CMP) near3 composition	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 12:58
S73	626	fatty near acid same (surfactant or (surface near active)) and (polishing or CMP) near3 composition	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 12:58
S74	89	fatty near acid same (surfactant or (surface near active)) and ((polishing or CMP) near3 composition).ti	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 12:58
S75	60	fatty near acid same (surfactant or (surface near active)) and ((polishing or CMP) near3 composition).ti and (silica or alumina or titania or titanium)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 13:16
S76	14	fatty near acid same (surfactant or (surface near active)) and ((polishing or CMP) near3 composition).ti and (silica or alumina or titanium or titanium) and azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 13:16
S77	40	fatty near acid same (surfactant or (surface near active)) and ((polishing or CMP) near3 composition).ti and (silica or alumina or titania or titanium) and (triazole or benzotriazole or azole)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 13:17
S78	2	("5976414").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/12/19 15:29
S79	0	((polyvinyl near tetrazole) or (poly near vinyl near tetrazole)) and (polishing or CMP) near3 composition	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 15:35
S80	24	((polyvinyl near tetrazole) or (poly near vinyl near tetrazole))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 15:36
S81	0	((polyvinyl near tetrazole) or (poly near vinyl near tetrazole)) and (polishing or abrading or planarizing or planarization)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 15:36

S82	12163	vinylimidazole or (vinyl near imidazole) or "vinyl-imidazole"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 15:39
S83	43	(vinylimidazole or (vinyl near imidazole) or "vinyl-imidazole") and (polishing or CMP) near3 composition	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 15:39
S84	2	("6410497").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/12/19 16:02
S85	0	S84 and (bleach near stabilizers)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 16:02
S86	1	S84 and (bleach near stabilizers)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 16:02
S87	1	(vinylimidazole or (vinyl near imidazole) or "vinyl-imidazole") and (polishing or CMP) near3 composition and (bleach near stabilizers)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 16:02
S88	1892	438/427.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:09
S89	6148	51/307-309.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:09
S90	2561	451/5.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:09
S91	1093	106/3.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:09
S92	1136	216/99.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:09
S93	1030	216/101-102.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:09
S94	13341	S88 S89 S90 S91 S92 S93	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:09

S95	1	S94 and vinyl near5 azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:09
S96	2	("20070082456").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/12/19 17:13
S97	2	S96 and azole with vinyl	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:13
S98	621	(polymerization or polymerize) with (vinylimidazole or (vinyl near imidazole))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:19
S99	786	(polymerization or polymerize) same (vinylimidazole or (vinyl near imidazole)) same ((acrylic near acid) or (methacrylic near acid) or (methyl near acrylate))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:19
S100	972	(polymerization or polymerize) same (vinylimidazole or (vinyl near imidazole)) same ((acrylic near acid) or (methacrylic near acid) or (methyl near acrylate) or (vinyl near acetate) or styrene or acryloylmorpholine)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:20
S101	85509	(polymerization or polymerize) same (vinylimidazole or (vinyl near imidazole)) same ((acrylic near acid) or (methacrylic near acid) or (methyl near acrylate) or (vinyl near acetate) or styrene or acryloylmorpholine) and polishing or CMP	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:20
S102	9	(polymerization or polymerize or polymerizing) same (vinylimidazole or (vinyl near imidazole)) same ((acrylic near acid) or (methacrylic near acid) or (methyl near acrylate) or (vinyl near acetate) or styrene or acryloylmorpholine) and (polishing or CMP)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/19 17:20

S103	1	WO-02067309-\$.did.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 09:14
S104	0	S103 and vinyl	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 09:15
S105	0	S103 and "1-vinylimidazole"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 09:15
S106	0	S103 and azole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 09:15
S107	264	vinylimidazole near10 polymeriz\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:12
S108	190	vinylimidazole near5 polymeriz\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:12
S109	0	vinylimidazole near5 polymeriz\$4 and ((polishing or abrading or planarizing or planarization or lapping) near composition).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:12
S110	0	vinylimidazole near5 polymeriz\$4 and ((polishing or abrading or planarizing or planarization or lapping) near2 composition).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:13
S111	5	vinylimidazole near5 polymerization and ((polishing or abrading or planarizing or planarization or lapping) near2 composition).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:13
S112	55	imidazole near10 (inhibiting or inhibitor) near10 (polymer or polymerization)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:15
S113	105	imidazole near10 (inhibiting or inhibitor) near10 (polymer or copolymer or copolymerization or polymerization)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:15

S114	5	imidazole near10 (inhibiting or inhibitor) near10 (polymer or copolymer or copolymerization or polymerization) and ((polishing or abrading or planarizing or planarization or lapping) near2 composition).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:15
S115	7	imidazole near10 (inhibiting or inhibitor) near10 (polymer or copolymer or copolymerization or polymerization) and (polishing or abrading or planarizing or planarization or lapping) near2 composition	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:15
S116	7	imidazole near10 (inhibiting or inhibitor) near10 (polymer or copolymer or copolymerization or polymerization) and (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical)) near2 composition	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:16
S117	7	imidazole near10 (inhibiting or inhibitor) near10 (polymer or copolymer or copolymerization or polymerization) and (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical)) near5 composition	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:16
S118	24	imidazole near10 (inhibiting or inhibitor) near10 (polymer or copolymer or copolymerization or polymerization) and corrosion near5 (inhibiting or inhibitor)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:16
S119	24	(vinylimidazole or imidazole) near10 (inhibiting or inhibitor) near10 (polymer or copolymer or copolymerization or polymerization) and corrosion near5 (inhibiting or inhibitor)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:18

S120	10	(vinylimidazole or imidazole) near10 (inhibiting or inhibitor) near10 (polymer or copolymer or copolymerization or polymerization) and corrosion near5 (inhibiting or inhibitor) and (polishing or planarizing or planarization or lapping or CMP or (chemical near mechanical))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:19
S121	12	(vinylimidazole or imidazole) near10 (inhibiting or inhibitor) near10 (polymer or copolymer or copolymerization or polymerization) and (polishing or planarizing or planarization or lapping or CMP or (chemical near mechanical))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:24
S122	12	S121 and (vinylimidazole or imidazole) near10 (inhibiting or inhibitor) near10 (polymer or copolymer or copolymerization or polymerization)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:25
S123	2	("6562719").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2009/06/11 12:26
S124	1	S123 and (vinylimidazole or imidazole) near10 (inhibiting or inhibitor) near10 (polymer or copolymer or copolymerization or polymerization)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:26
S125	16	(content or amount) with ((film near forming) or (corrosion near (inhibitor or inhibiting))) with (known or usually or conventional or conventionally or skilled) and (polishing or lapping or planarizing or planarization or abrading or CMP or (chemical near mechanical)). ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 12:30
S126	1907	438/427.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 14:10

S127	6244	51/307-309.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 14:10
S128	2642	451/5.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 14:10
S129	1107	106/3.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 14:10
S130	1150	216/99.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 14:10
S131	1033	216/101-102.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 14:10
S132	13558	S126 S127 S128 S129 S130 S131	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 14:10
S133	39	S132 and ("film-forming" or film near forming) near10 (content or amount)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/11 14:10
S134	252	((water near2 soluble) or "water-soluble") same ("poly (vinylimidazole)" or (poly near2 vinylimidazole))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 14:59
S135	157	((water near2 soluble) or "water-soluble") with ("poly (vinylimidazole)" or (poly near2 vinylimidazole))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 14:59
S136	0	((water near2 soluble) or "water-soluble") with ("poly (vinylimidazole)" or (poly near2 vinylimidazole)) same (polishing or abrading or planarizing or planarization or lapping)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 14:59
S137	3	((water near2 soluble) or "water-soluble") with ("poly (vinylimidazole)" or (poly near2 vinylimidazole)) and (polishing or abrading or planarizing or planarization or lapping)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:00

S138	0	((water near2 soluble) or "water-soluble") with ("poly (vinylimidazole)" or (poly near2 vinylimidazole)) same (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:00
S139	0	((water near2 soluble) or "water-soluble") with ("poly (vinylimidazole)" or (poly near2 vinylimidazole)) and (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical)). ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:00
S140	739	(surfactant or (surface near2 active) or "surface-active") same (alkylaromatic or sulfonic or polyoxyethylene or phosphoric) and polishing. ti.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:13
S141	1907	438/427.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:13
S142	6244	51/307-309.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:13
S143	2642	451/5.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:13
S144	1107	106/3.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:13
S145	1150	216/99.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:13
S146	1033	216/101-102.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:13
S147	13558	S141 S142 S143 S144 S145 S146	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:13

S148	138	S147 and S140	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:13
S149	54	S148 and glycine	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:13
S150	52	S148 and glycine and (polishing or abrading or lapping or planarizing or planarization or CMP or (chemical near mechanical)). ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:13
S151	30	S148 and glycine same amino near acid and (polishing or abrading or lapping or planarizing or planarization or CMP or (chemical near mechanical)). ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 15:13
S152	134	(generally or known or usually or conventionally or conventional or skilled or widely) same (oxidizing or peroxide or permanganate or dipersulfate or monopersulfate) with (amount or content) and (polishing or planarizing or planarization or lapping or CMP or (chemical near mechanical) or abarading). ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 16:05
S153	135	(generally or known or usually or conventionally or conventional or skilled or widely) same (oxidizing or peroxide or permanganate or dipersulfate or monopersulfate) with (amount or content) and (polishing or planarizing or planarization or lapping or CMP or (chemical near mechanical) or abrading).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 16:05

S154	68	(generally or known or usually or conventionally or conventional or skilled or widely) with (oxidizing or peroxide or permanganate or dipersulfate or monopersulfate) with (amount or content) and (polishing or planarizing or planarization or lapping or CMP or (chemical near mechanical) or abrading).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 16:05
S155	48	(generally or known or usually or conventionally or conventional or skilled or widely) with (oxidizing or peroxide or permanganate or dipersulfate or monopersulfate) near5 (amount or content) and (polishing or planarizing or planarization or lapping or CMP or (chemical near mechanical) or abrading).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 16:05
S156	75	benzotriazole same ((film near forming) or "film-forming") same (content or amount) and (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 16:38
S157	71	benzotriazole same ((film near forming) or "film-forming") same (content or amount) and (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical)).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 16:39
S158	72	(benzotriazole or "BTA") same ((film near forming) or "film-forming") same (content or amount) and (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical)).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 16:40

SI59	2	((benzotriazole or "BTA") same ((film near forming) or "film-forming") same (content or amount) with (known or usual or usually or generally or skilled or widely or conventionally or conventionally) and (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical)).ab.	US-PGPUB; USPAT; USOCR; EPC; JPO; DERWENT	OR	ON	2009/06/15 16:40
SI60	16	((film near forming) or "film-forming") same (content or amount) with (known or usual or usually or generally or skilled or widely or conventionally or conventionally) and (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical)).ab.	US-PGPUB; USPAT; USOCR; EPC; JPO; DERWENT	OR	ON	2009/06/15 16:41
SI61	34	((film near forming) or "film-forming" or corrosion near inhibit\$4) same (content or amount) with (known or usual or usually or generally or skilled or widely or conventionally or conventionally) and (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical)).ab.	US-PGPUB; USPAT; USOCR; EPC; JPO; DERWENT	OR	ON	2009/06/15 16:42
SI62	366365	((film near forming) or "film-forming" or corrosion near inhibit\$4) with3 ("BTA" or benotriazole) (content or amount) and (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical)).ab.	US-PGPUB; USPAT; USOCR; EPC; JPO; DERWENT	OR	ON	2009/06/15 16:44
SI63	336438	((film near forming) or "film-forming" or corrosion near inhibit\$4) with3 ("BTA" or benotriazole) and (content or amount) and (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical)).ab.	US-PGPUB; USPAT; USOCR; EPC; JPO; DERWENT	OR	ON	2009/06/15 16:45

S164	366365	((film near forming) or "film-forming" or corrosion near inhibit\$4) with3 ("BTA" or benotriazole) with3 (content or amount) and (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical)).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 16:45
S165	35	((film near forming) or "film-forming" or corrosion near inhibit\$4) with ("BTA" or benotriazole) with (content or amount) and (polishing or abrading or planarizing or planarization or lapping or CMP or (chemical near mechanical)).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/15 16:45
S166	0	((polymer or polymeriz\$4) near20 (vinylimidazole or vinyl near imidazole)) with (content or amount) same (polishing or planarizing or planarization or abrading or lapping or CMP or chemical near mechanical)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 09:21
S167	2	((polymer or polymeriz\$4) near20 (vinylimidazole or vinyl near imidazole)) with (content or amount) and (polishing or planarizing or planarization or abrading or lapping or CMP or chemical near mechanical)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 09:21
S168	46	azole near10 (content or amount) and (polishing or abrading or lapping or planarizing or planarization or CMP or chemical near mechanical).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 09:23
S169	39	azole near5 (content or amount) and (polishing or abrading or lapping or planarizing or planarization or CMP or chemical near mechanical).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 09:23
S170	49	polyelectrolyte same (content or amount) and (polishing or abrading or lapping or planarizing or planarization or CMP or chemical near mechanical).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 09:24

S171	0	polyelectrolyte same azole same (content or amount) and (polishing or abrading or lapping or planarizing or planarization or CMP or chemical near mechanical).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 09:24
S172	0	polyelectrolyte near30 azole same (content or amount) and (polishing or abrading or lapping or planarizing or planarization or CMP or chemical near mechanical).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 09:24
S173	3	polyelectrolyte same vinylimidazole same (content or amount) and (polishing or abrading or lapping or planarizing or planarization or CMP or chemical near mechanical).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 09:25
S174	7	"more" near3 "azole" same (content or amount) and (polishing or abrading or lapping or planarizing or planarization or CMP or chemical near mechanical).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 09:26
S175	2	polyvinylimidazole with corrosion near inhibit\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 09:35
S176	2	polyvinylimidazole with corrosion near inhibit\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 09:35
S177	161	oxidizing near agent same (amount or content) same (effective or exhibit or prefer \$4 or enahnc\$4 or impart\$4 or decreas\$4 or benefit or better) and (polishing or planarizing or planarization or lapping or abrading or CMP or chemical near mechanical).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 10:31

S178	9	oxidizing near agent near10 (generally or usually or usual or conventionally or conventionl or skilled or widely or known) same (amount or content) same (effective or exhibit or prefer \$4 or enahnc\$4 or impart\$4 or decreas\$4 or benefit or better) and (polishing or planarizing or planarization or lapping or abrading or CMP or chemical near mechanical).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 10:31
S179	11	oxidizing near agent same (amount or content) near10 (generally or usually or usual or conventionl or skilled or widely or known) same (effective or exhibit or prefer \$4 or enahnc\$4 or impart\$4 or decreas\$4 or benefit or better) and (polishing or planarizing or planarization or lapping or abrading or CMP or chemical near mechanical).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/06/16 10:32

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